

## SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Marianne Padgett Examiner #: 65627 Date: 3/9/04  
Art Unit: 1702 Phone Number 301-272-1425 Serial Number: 10/635,514  
Mail Box and Bldg/Room Location: REM 8D71 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

\*\*\*\*\*  
Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Resist composition

Inventors (please provide full names): Kameko et al (see attached)

Earliest Priority Filing Date: 1/31/02 For PCT parent

\*For Sequence Searches Only\* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Cyclopolymerization, fluorinated diene  
and "blocked" acidic groups"

see claims 1 and 2 (attached) for chemical  
formula of fluorinated diene

## STAFF USE ONLY

	Type of Search	Vendors and cost where applicable
Searcher: <u>ED</u>	NA Sequence (#) _____	STN <u>\$ 241.06</u>
Searcher Phone #: _____	AA Sequence (#) _____	Dialog _____
Searcher Location: _____	Structure (#) <u>5</u> <u>(subset)</u>	Questel/Orbit _____
Date Searcher Picked Up: _____	Bibliographic <u>✓</u>	Dr.Link _____
Date Completed: <u>3-12-04</u>	Litigation _____	Lexis/Nexis _____
Searcher Prep & Review Time: <u>5</u>	Fulltext _____	Sequence Systems _____
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Online Time: <u>70</u>	Other _____	Other (specify) _____

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FILE 'LREGISTRY'

L1 STR  
L2 STR

FILE 'REGISTRY'

L3 9 S L2  
L4 STR L2  
L5 11 S L4  
L6 346 S L4 FUL  
DEL CAM?/A  
SAV L6 PAD514/A  
L7 0 S L1 SSS SAM SUB=L6  
L8 12 S L1 SSS FUL SUB=L6  
SAV L8 PAD514A/A

FILE 'CAOLD'

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L10 20 S L6

FILE 'HCAPLUS'

L11 7 S L8  
L12 194 S L6  
L13 159068 S RESIST OR RESISTS OR PHOTORESIST? OR MASK? OR PHOTOMASK  
L14 22 S L12 AND L13  
L15 6 S L11 AND L13  
L16 11225 S BLOCK? (2A)ACID?  
L17 4620 S ACID? (2A)LABIL?  
L18 46990 S ACTIV? (2A) (HYDROGEN# OR H)  
L19 3 S L12 AND L16  
L20 2 S L12 AND L17  
L21 0 S L12 AND L18

FILE 'REGISTRY'

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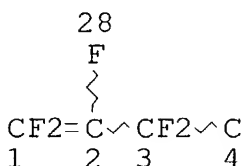
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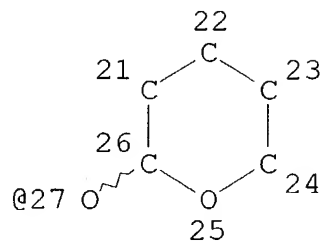
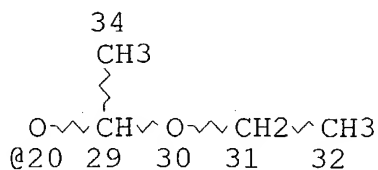
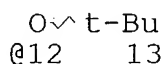
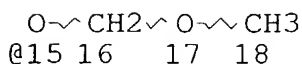
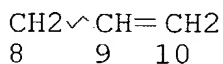
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 L26                    21 S (L24 OR L25) AND L13  
 L27                    13555 S PAG OR PAGES OR PHOTOACID? OR PHOTOGENERAT? OR PHOTO(2A)  
 L28                    7 S L12 AND L27  
 L29                    13 S L11 OR L15 OR L19 OR L20 OR L28  
 L30                    10 S (L14 OR L26) NOT L29

FILE 'REGISTRY'

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L1                    STR



G1 6



VAR G1=12/15/20/27

NODE ATTRIBUTES:

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DEFAULT ECLEVEL IS LIMITED

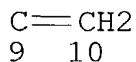
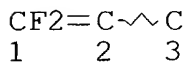
GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 28

STEREO ATTRIBUTES: NONE

L4                    STR



NODE ATTRIBUTES:

NSPEC IS RC AT 3

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED  
NUMBER OF NODES IS 5

STEREO ATTRIBUTES: NONE

L6 346 SEA FILE=REGISTRY SSS FUL L4  
L8 12 SEA FILE=REGISTRY SUB=L6 SSS FUL L1

100.0% PROCESSED 26 ITERATIONS  
SEARCH TIME: 00.00.01

12 ANSWERS

=> file hcaplus

FILE 'HCAPLUS'

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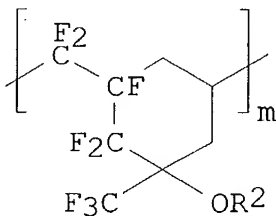
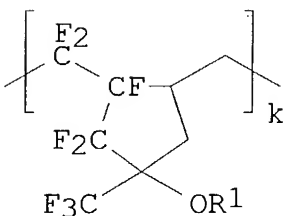
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L29 ANSWER 1 OF 13 HCAPLUS COPYRIGHT 2004 ACS on STN

2004:37354 Document No. 140:119866 **Photoresist** materials

with excellent transparency, alkali solubility, and plasma etching resistance and pattern formation method using them. Hatakeyama, Jun; Harada, Yuji; Kawai, Yoshio (Shin-Etsu Chemical Industry Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004012886 A2 2004|01|15, 36 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2002-167293 20020607.

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